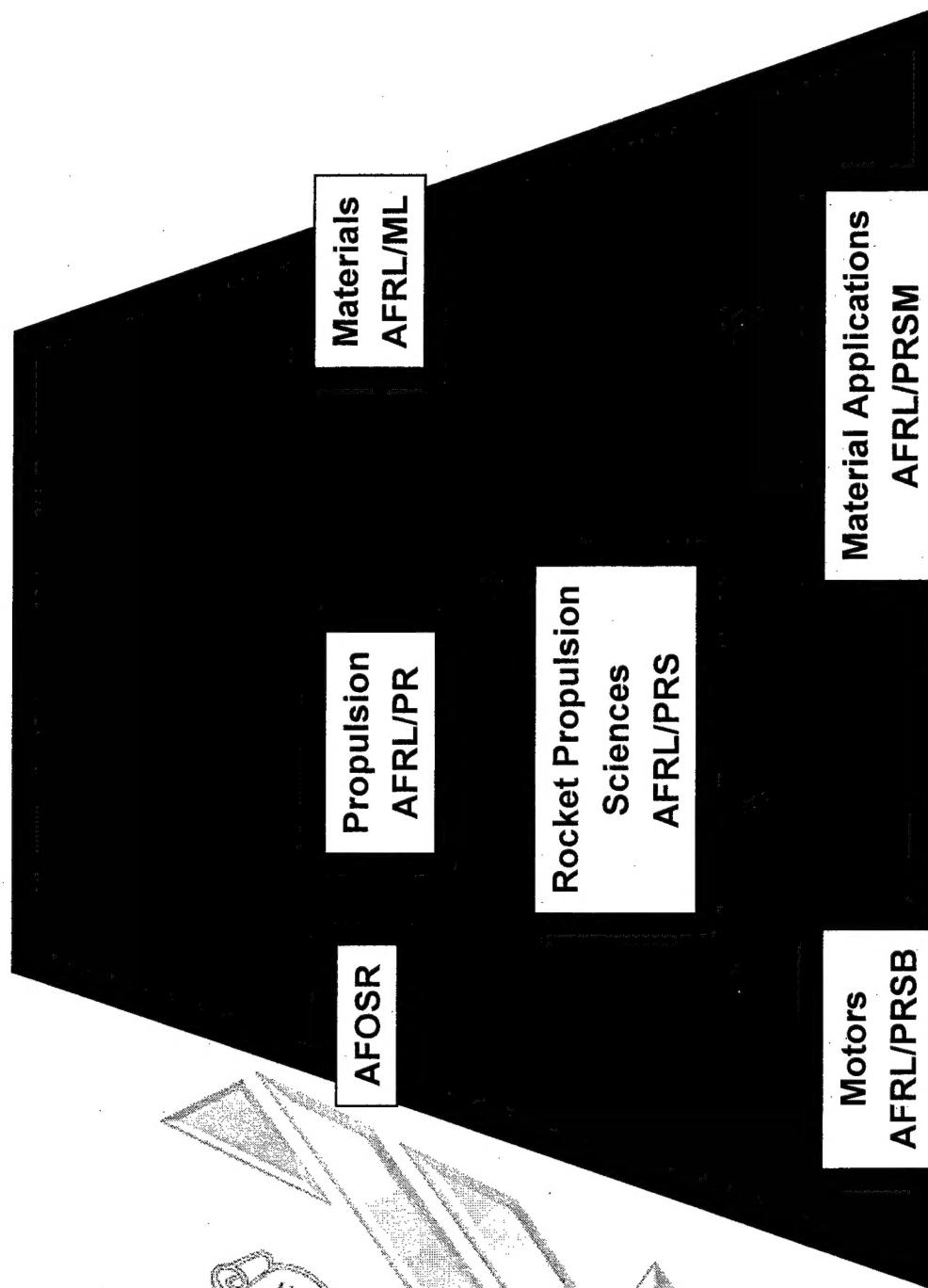
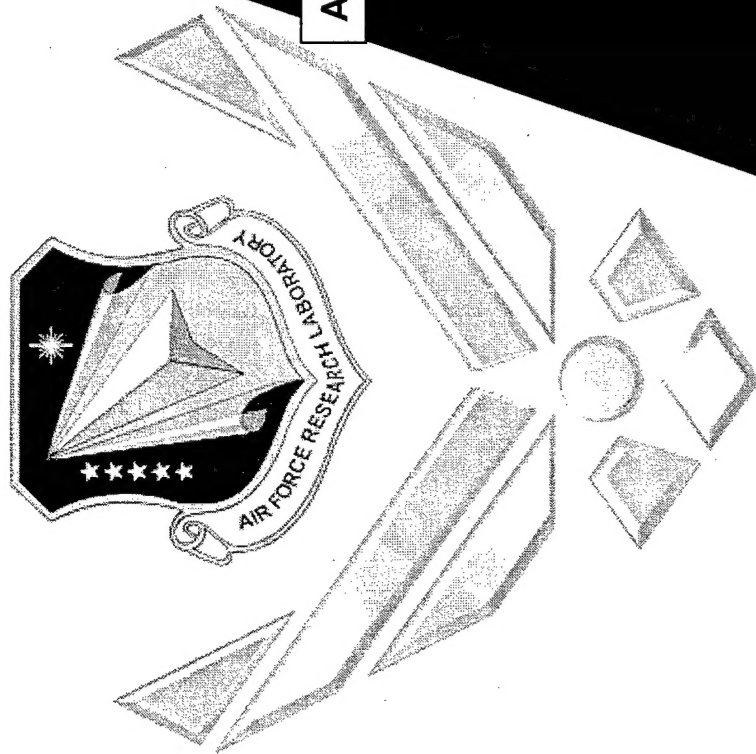


**REPORT DOCUMENTATION PAGE**Form Approved  
OMB No. 0704-0188

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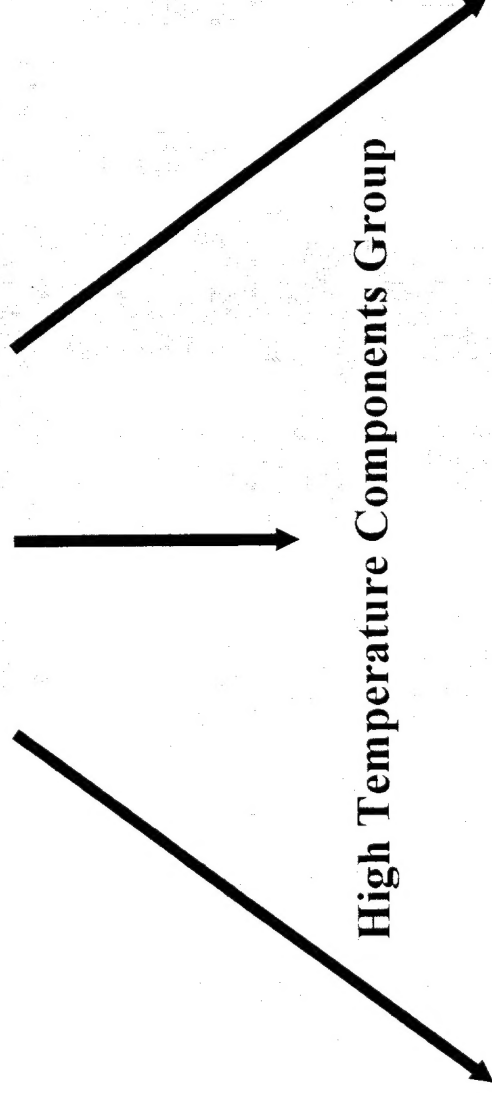
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<b>6. AUTHOR(S)</b>  Dr. Shawn H. Phillips				<b>5d. PROJECT NUMBER</b> 4847	
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# Materials Applications Research within the Propulsion Directorate of the Air Force Research Laboratory (AFRL/PRSM)



***“Seated within the Propulsion Directorate of the Air Force Research Laboratory, the Material Applications Branch has as its Mission to Apply and Transition Materials Technology to Rocket Propulsion.”***

**Dr. Shawn H. Phillips**  
Chief, AFRL/PRSM  
Air Force Research Lab, Edwards



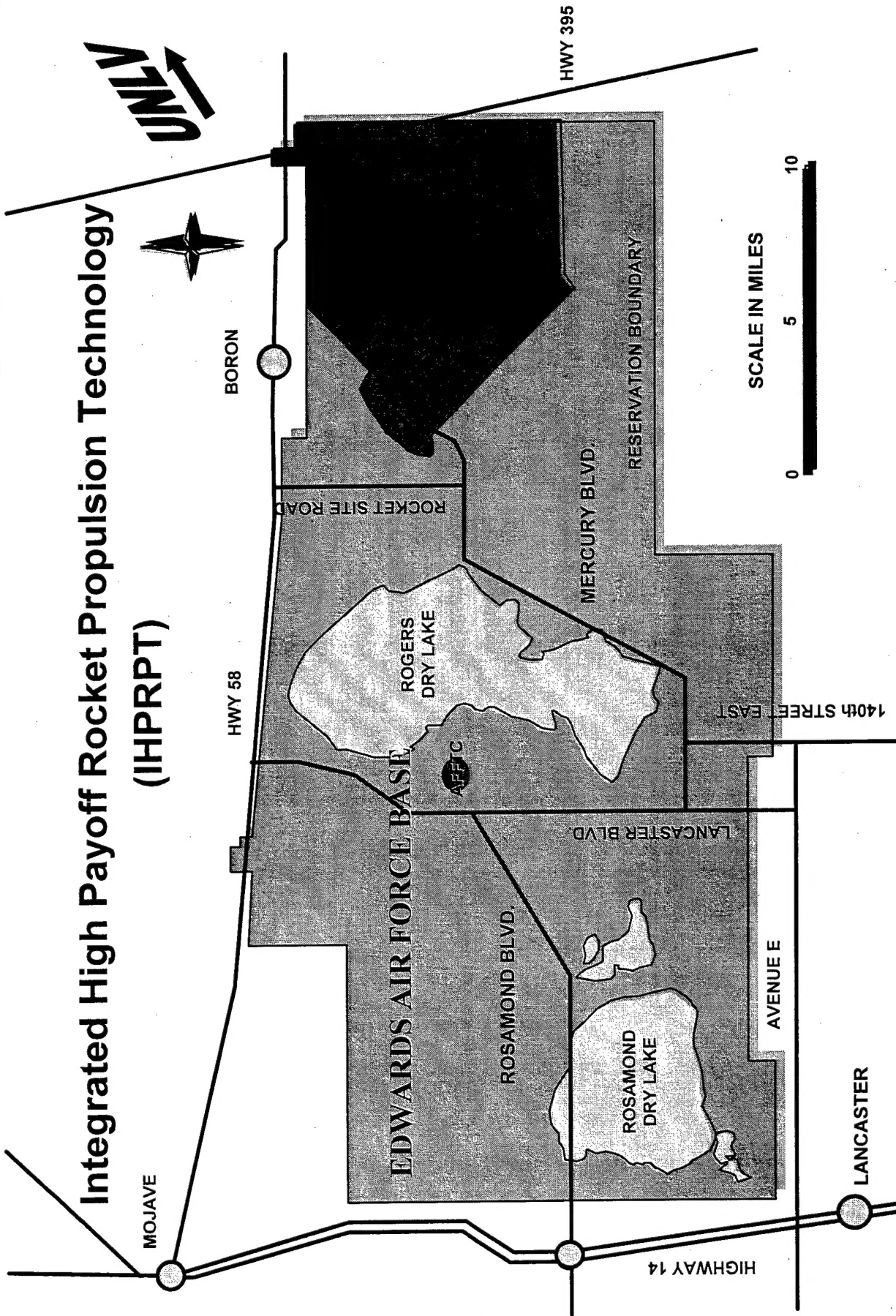
**High Temperature Components Group**

**Polymer Working Group**

**Fracture Mechanics Group**

# Air Force Research Laboratory (Edwards)

Integrated High Payoff Rocket Propulsion Technology  
(IHPRPT)





# **Research Focus within AFRL/PRSM**

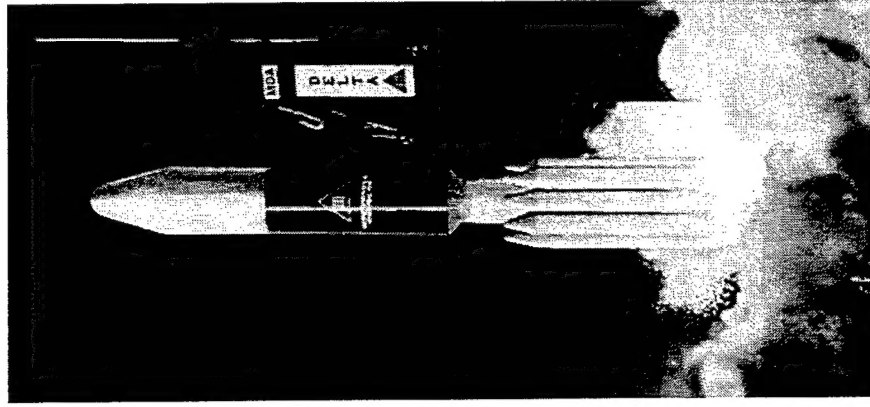


## **High Temperature Components**

- **Rapid Densification of Carbon-Carbon**
- **Microtube Technology**
- **Scale-up and Commercialization of Rapid Densification of Carbon-Carbon**

## **POSS Nanostructured Polymers**

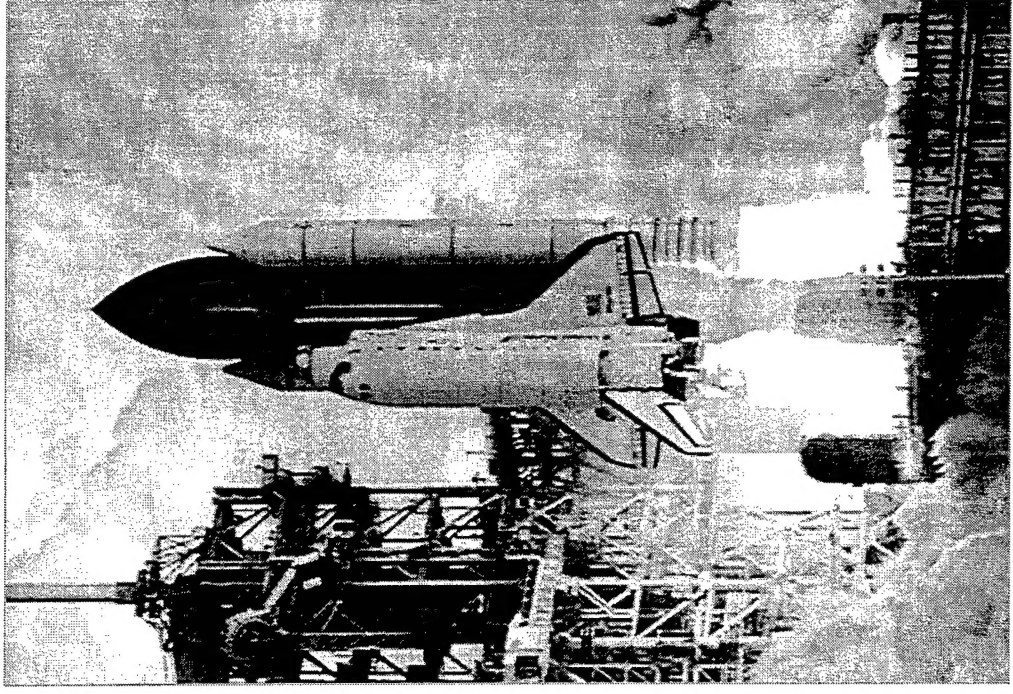
- **Structure/Property Relationships**
- **Thermo/Mechanical Improvement of Polymers**
- **Space-survivable Materials and Coatings**
- **Scale-up and Commercialization of POSS Nanotechnology**



# Rapid Densification of Carbon-Carbon



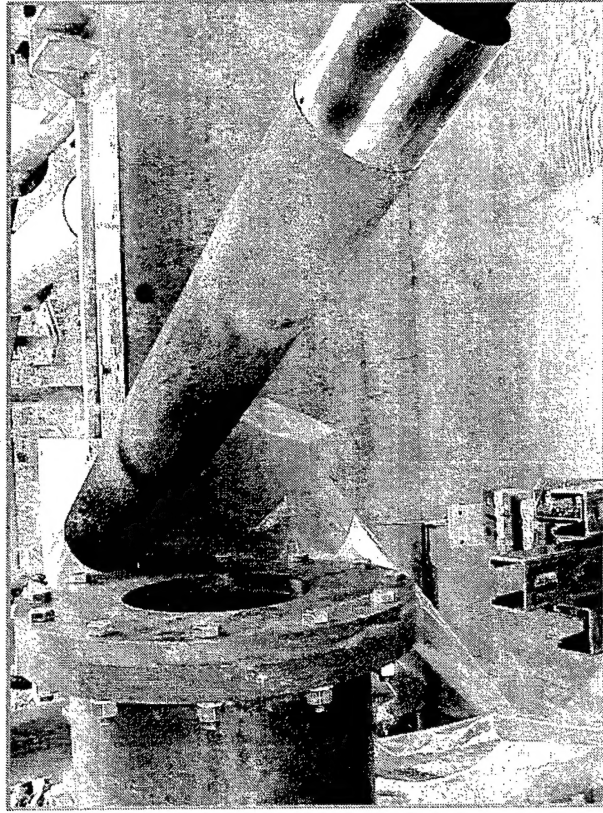
- Carbon-Carbon Advantages
  - Excellent High Temperature Structural Material
  - Very Reliable in Rocket Nozzles, Exit Cones, Nostips, and Leading Edges As Well As Aircraft Brakes
- Drawbacks to Carbon-Carbon
  - SOTA Production of Carbon-Carbon Is Very Expensive
  - Carbon-Carbon Oxidizes at High Temperature in the Presence of Oxidizers





## Objectives

- Decrease the processing time of Carbon-Carbon composites from many months to less than two weeks.
- Cut the densification cost in half.



**Carbon-Carbon part densified  
in less than two weeks**

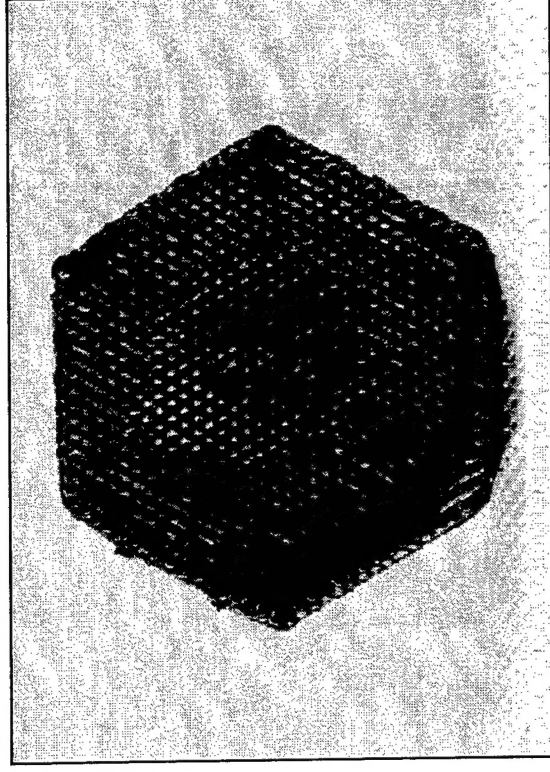
# Rapid Densification of Carbon-Carbon



## Technical Challenge:

- With Conventional Liquid Phase Processes There Is Incomplete Penetration of the Liquids Due To:

- a.) High Viscosity
- b.) High Surface Tension
- c.) Gassing of Precursor



- With Gas Phase Processes There Is Incomplete Penetration of the Gases Due to Their Decomposition on the Outer Surface

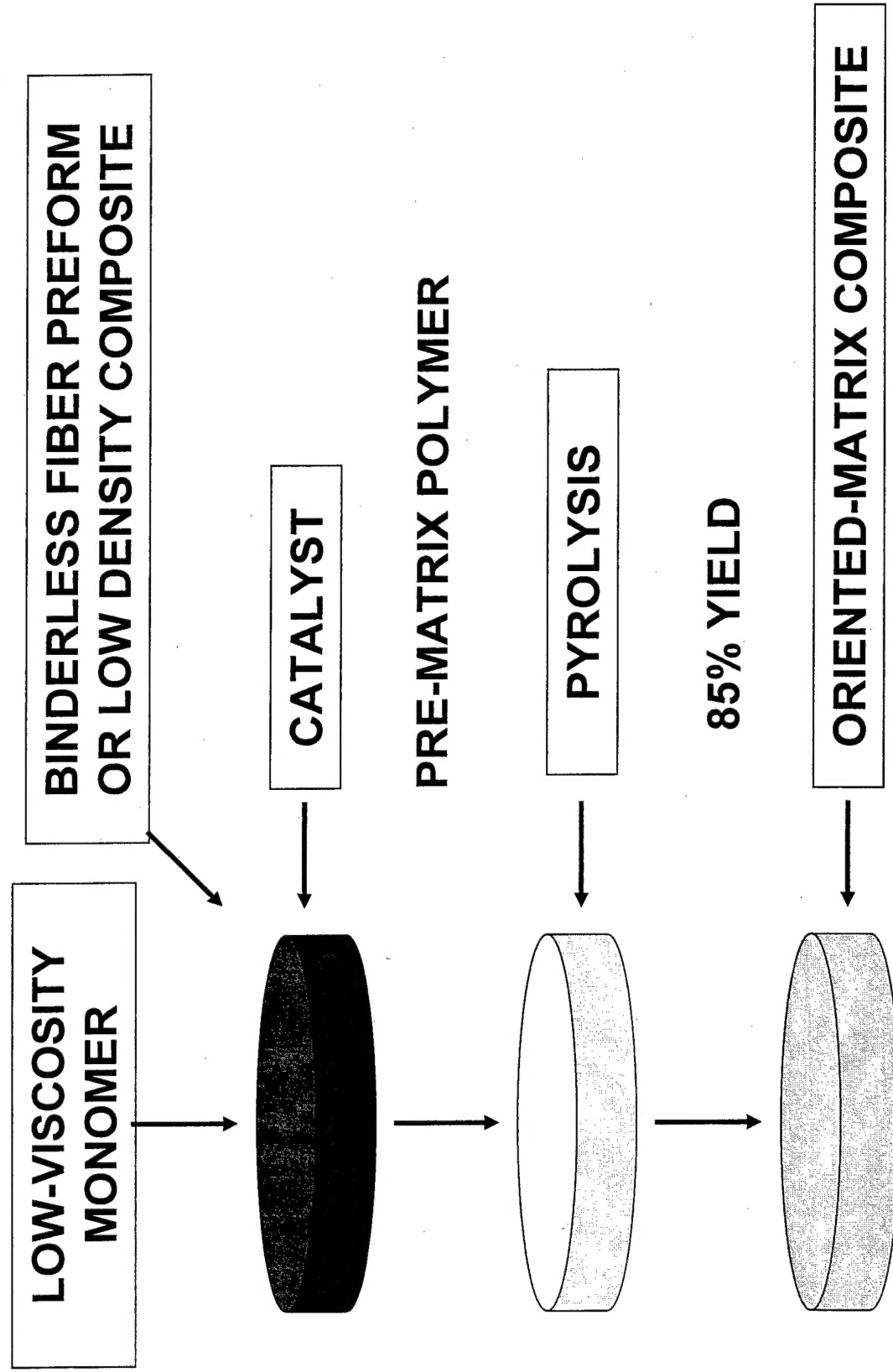
# **Rapid Densification of Carbon-Carbon**



## **Technical Approach:**

- For Liquid Processes Use an Impregnant That Has:
  - a.) A High Carbon to Hydrogen Ratio (Char Yield)
  - b.) Low Viscosity
  - c.) Wets the Fiber Preform.
- In Normal Processing It Is Impossible to Get This Combination of Properties
  - High Char Yield Needs High Molecular Weight
  - Low Viscosity and Wetting Require Low Molecular Weight

# In-Situ Formation of Carbon and Ceramic Matrices





# Process Advantages



- Very Uniform Density
- Can Densify Thick Composite
- Complex Geometries
- No Need to Graphitize
- No Need to Machine Between Densification Cycles



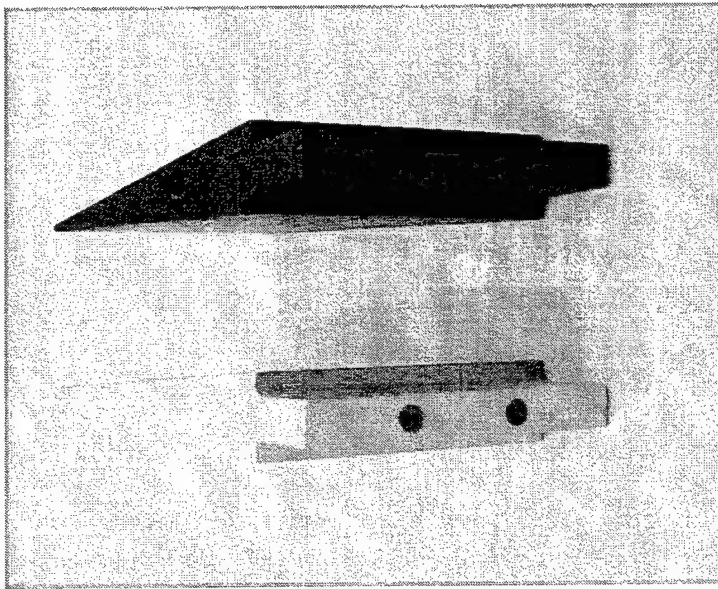
Compatible With Vapor-grown High-conductivity Fibers

- Dual Use: Carbon-Carbon Brakes and Electronic Thermal Management

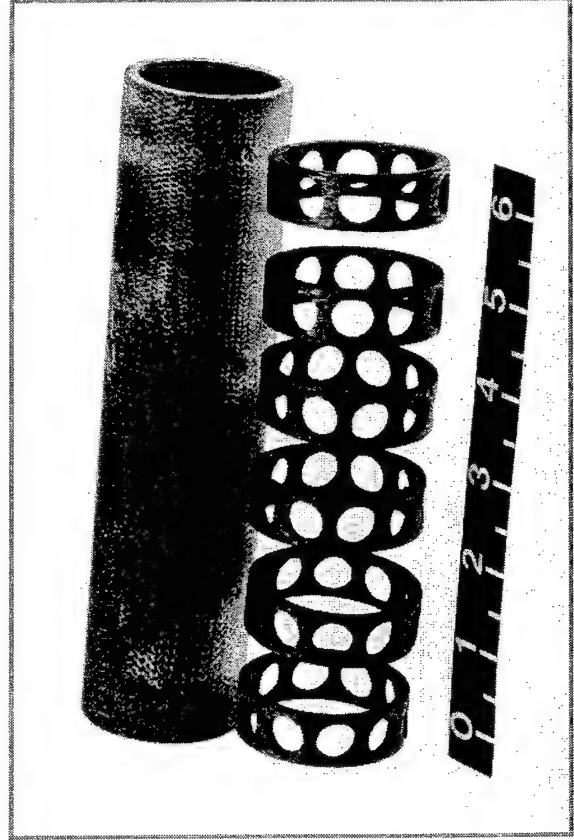
# Accomplishments



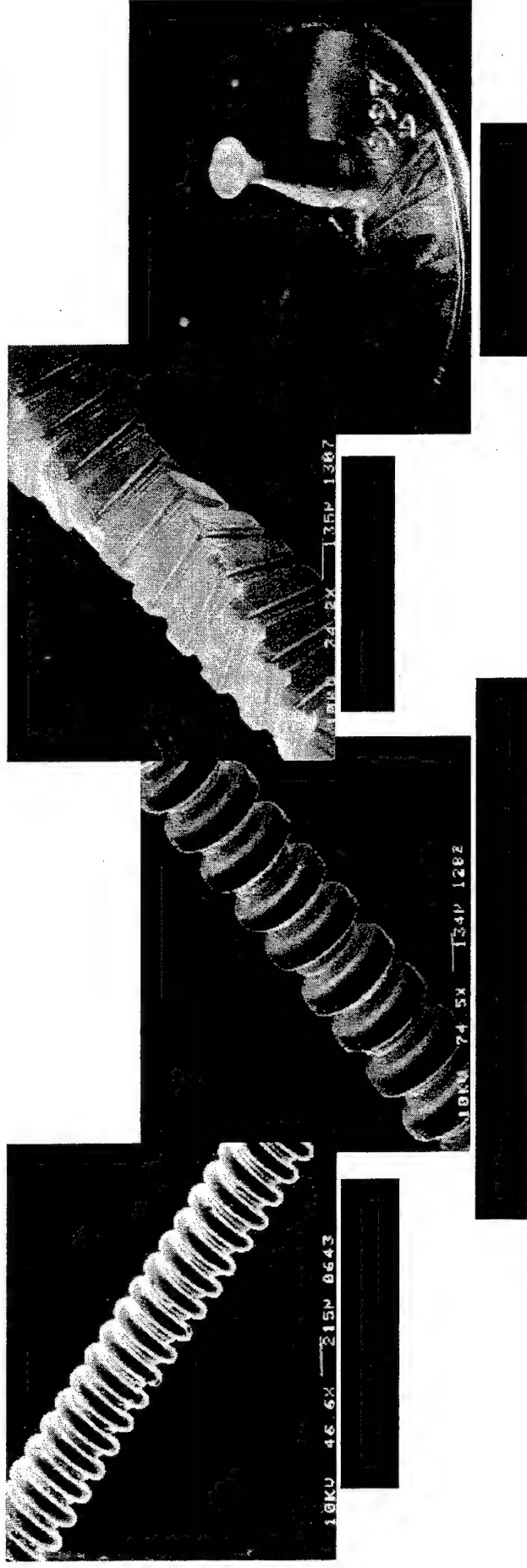
- Large Reactors have been Designed....Installed Allowing Scale-up to 18" Diameter and 60" Length.
- A Large (10" X 10" X 8") Preform and a 5' X 8" Tube Were Uniformly Densified With High Quality Matrix in 2 Weeks. (Not Possible With Other Processes)



- Technology Transfer to SMJ Carbon is ongoing with a cooperative research agreement.



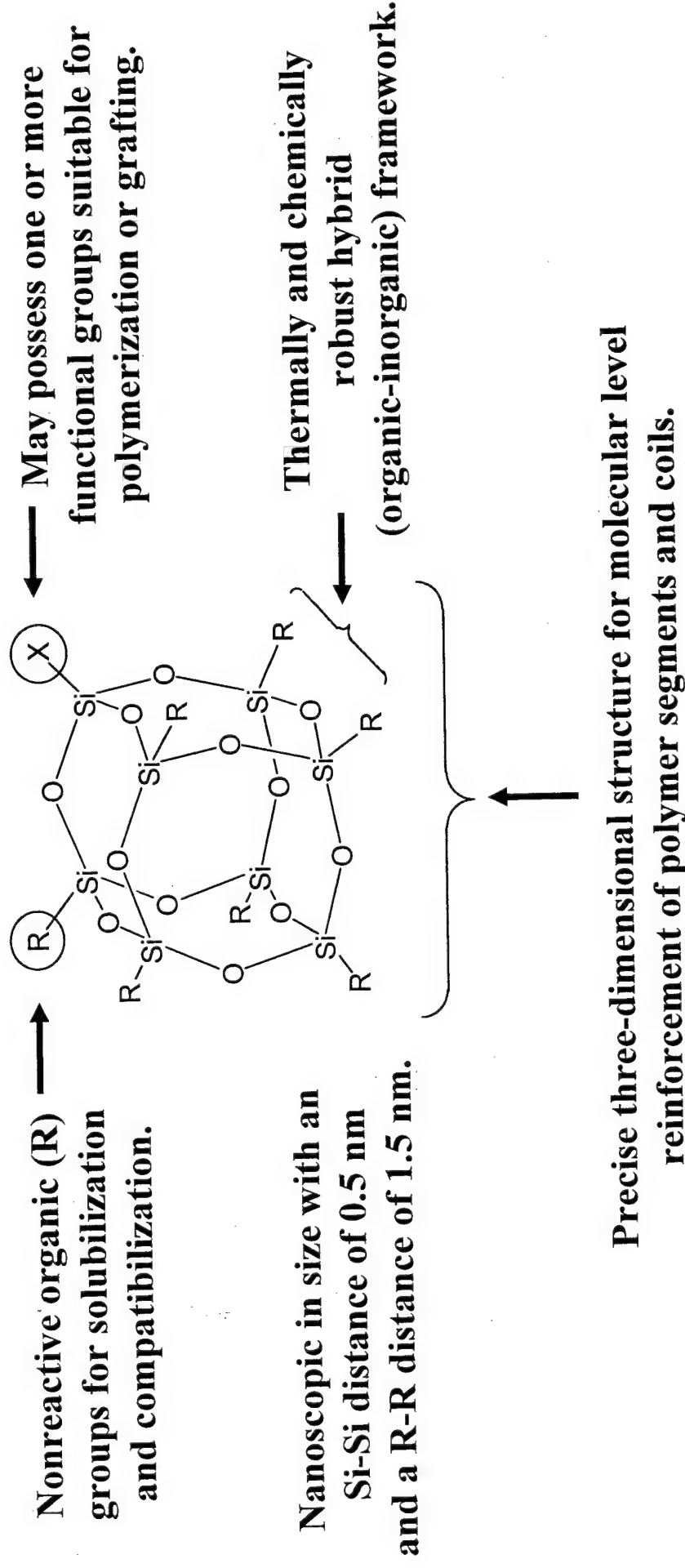
# Microdevice Fabrication and Micropropulsion



- Revolutionary method can make any 3-D micron scale shape from any material--1st reliable 3-D manufacturing method
- Heat exchangers, sensors, ducts and valves have all been successfully made using this process

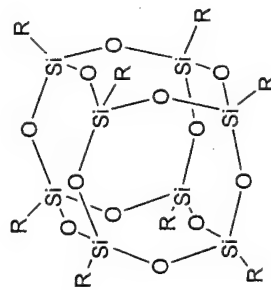
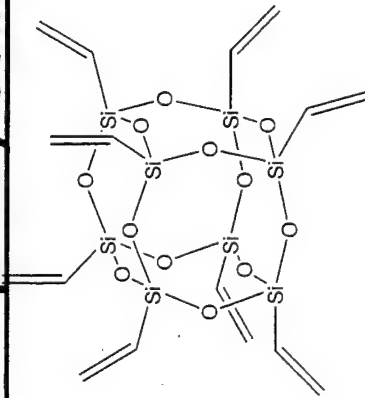
# Anatomy of a Polyhedral Oligomeric Silsesquioxane (POSS<sup>®</sup>) Molecule

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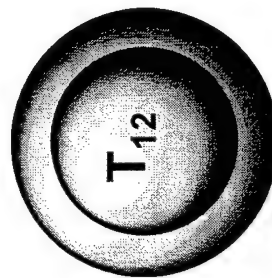
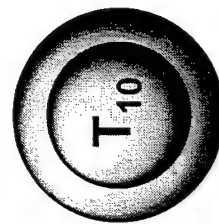
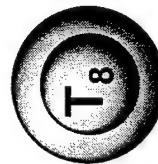


# POSS<sup>®</sup>

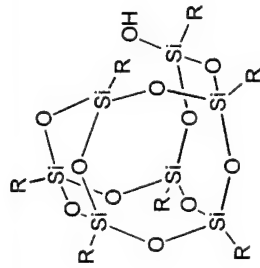
Completely Condensed



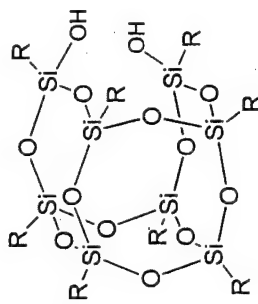
R = Me, Et, *i*-Bu, Cp,  
Cy, *i*-Octyl, Ph



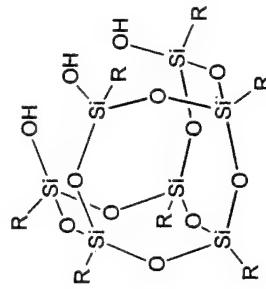
Incompletely Condensed



R = Cp, Cy, *i*-Bu



R = Cy, Cp, *i*-Bu, Et

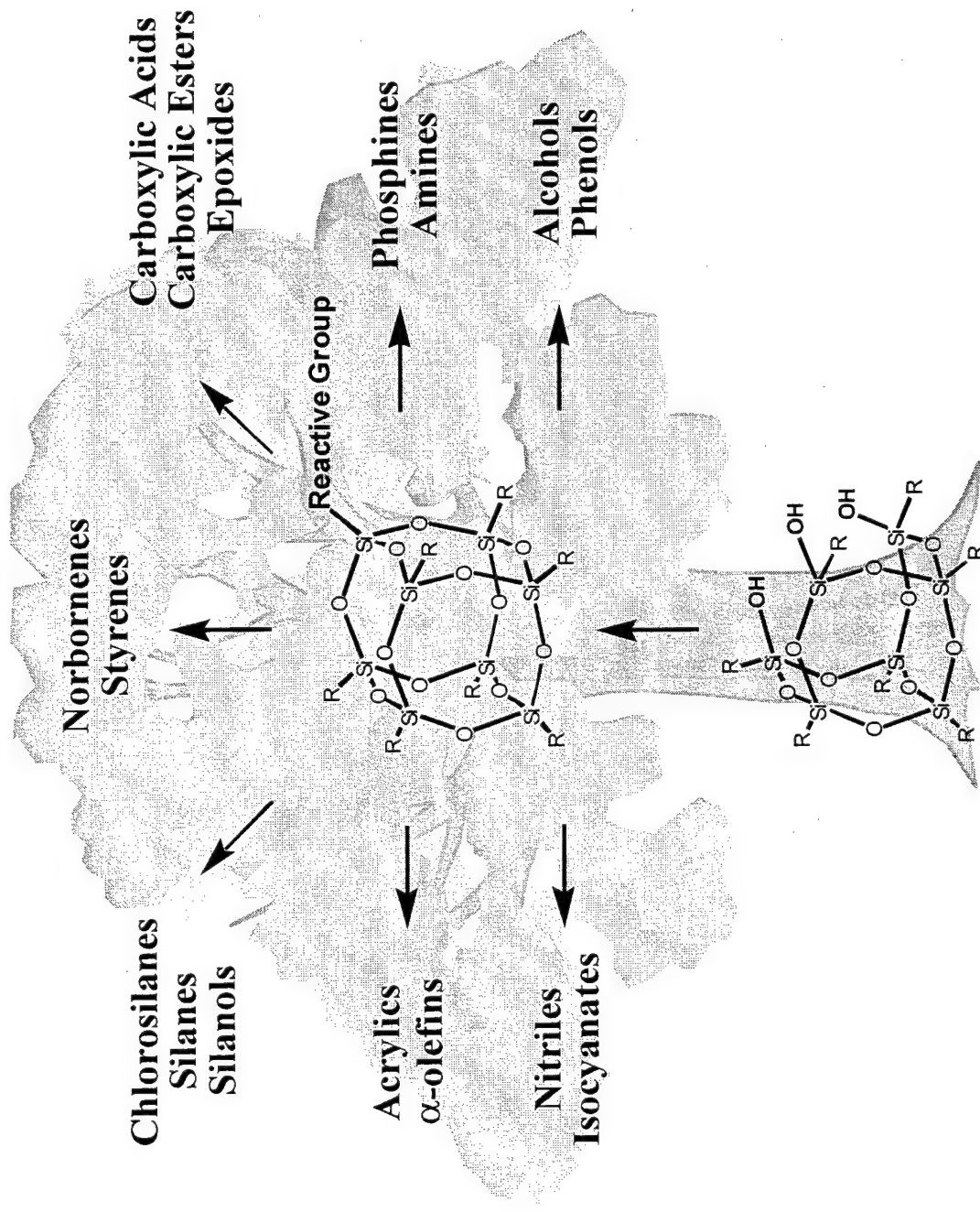


R = *i*-Butyl, Et

**>180 POSS Monomers are commercially available!!**

[www.hybridplastics.com](http://www.hybridplastics.com)

# Functionalized POSS<sup>®</sup>-Monomers

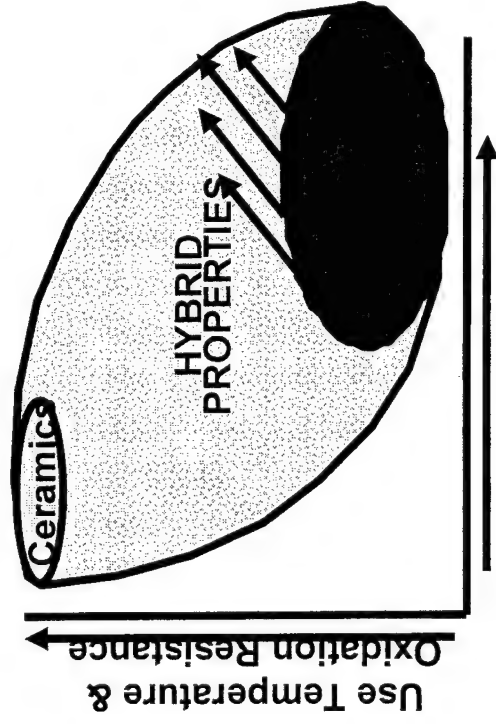


Hybrid Plastics currently offers over 180 Nanostructured<sup>™</sup> Chemicals

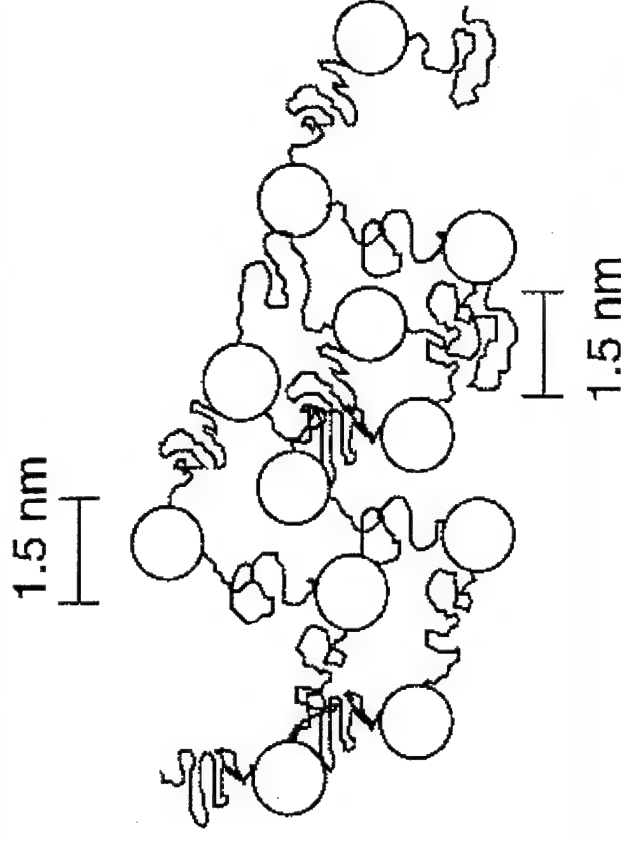


# Key Aspects of POSS<sup>®</sup> Technology

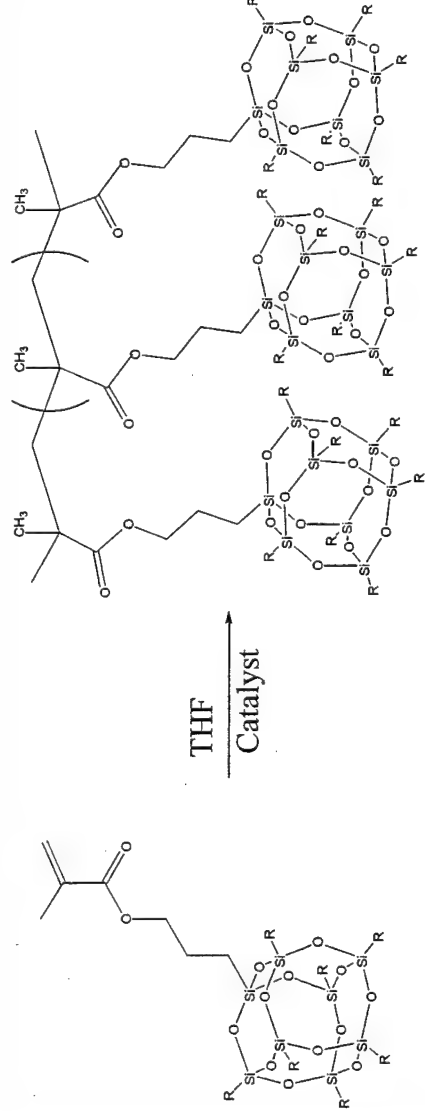
Hybrid (inorganic/organic) Composition



Nanostructured<sup>™</sup> Chemical Reinforcement



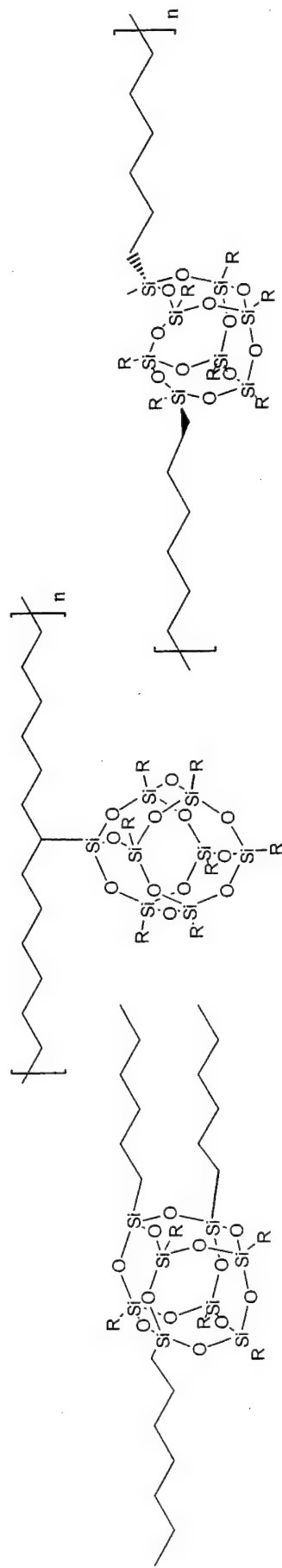
POSS<sup>™</sup> technology does not require manufacturers to retool or alter existing processes.



Lichtenhan et. al. *Macromolecules* **1993**, 26, 2141.  
Lichtenhan, *Polym. Mater. Encyclopedia* **1996**, 10, 7768.



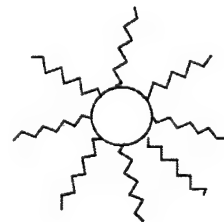
# POSS<sup>®</sup> Polymer Incorporation



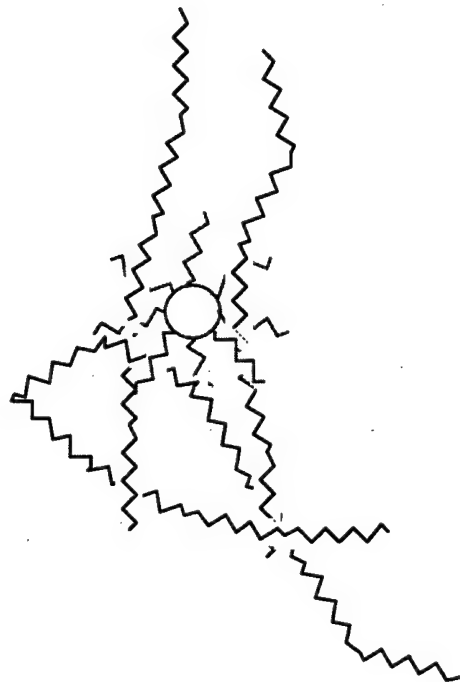
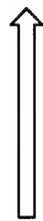
Cross-linker

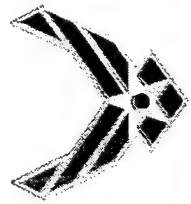
Pendant Polymer

Bead Copolymer

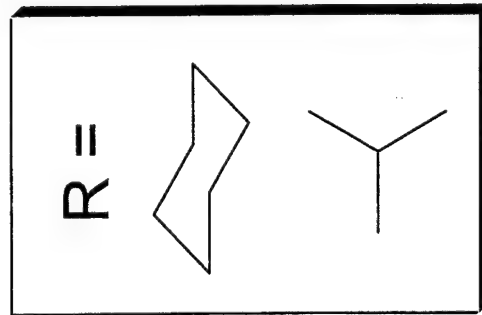
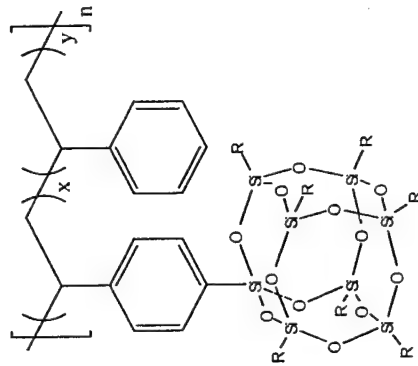
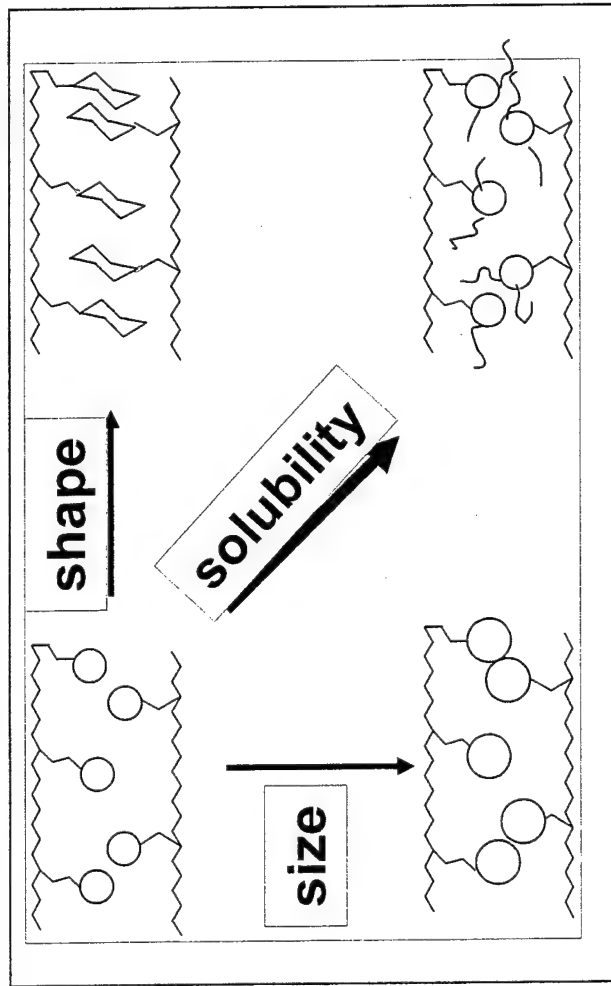


POSS Blending





# Structure/Property Relationships

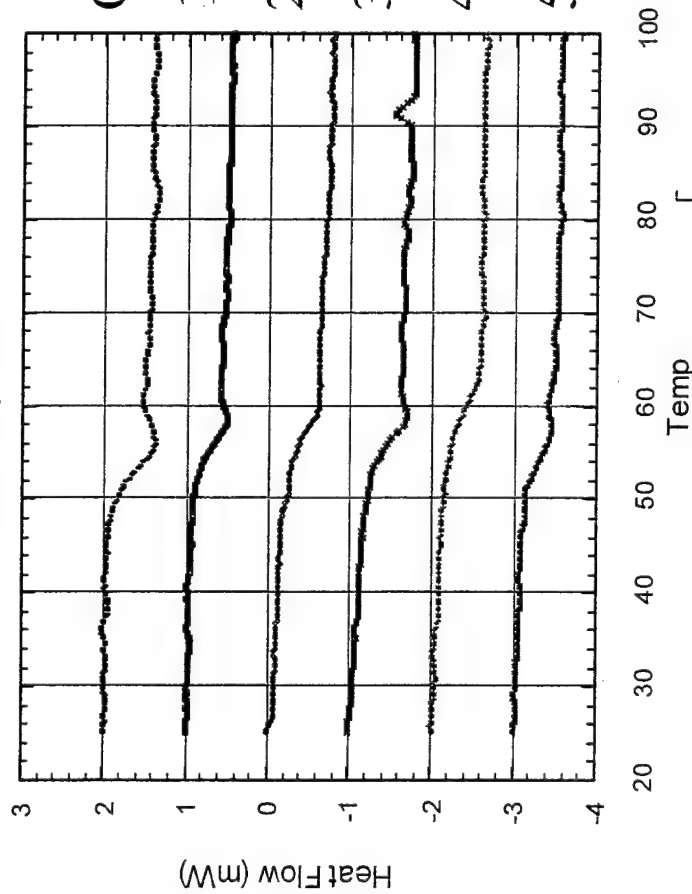


- Maximizing property enhancements through changes at the nano level
- Polymer compatibility vs. POSS/POSS interactions

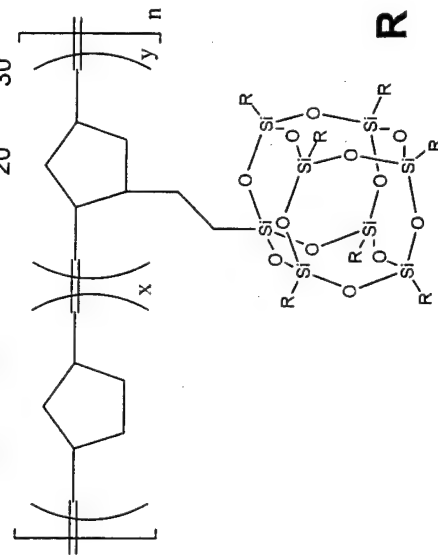
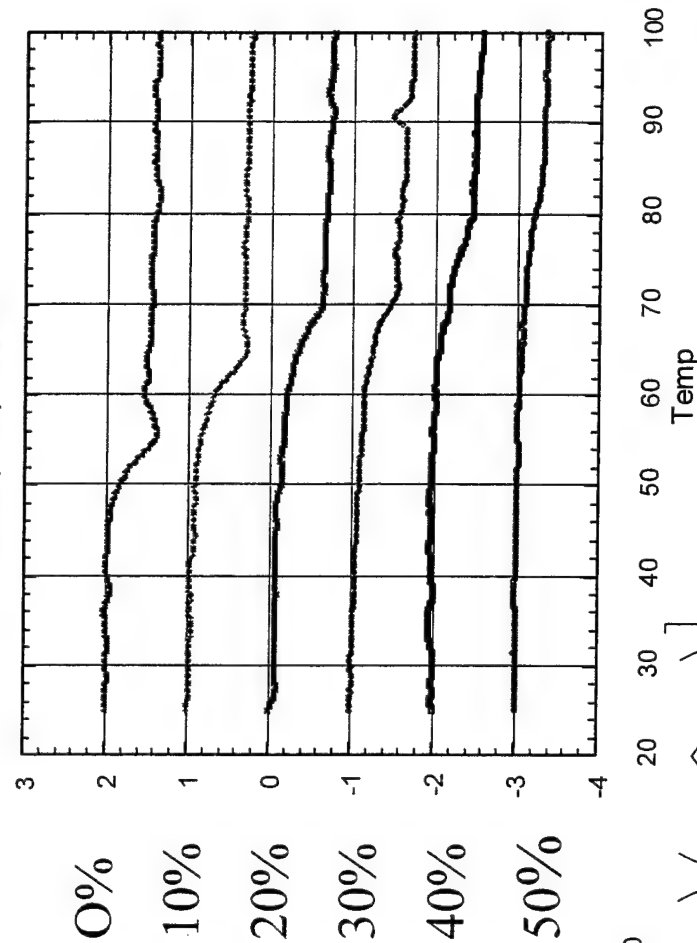


# DSC Data for POSS<sup>®</sup>-Norbornenes

CyNorb(0-50)-block



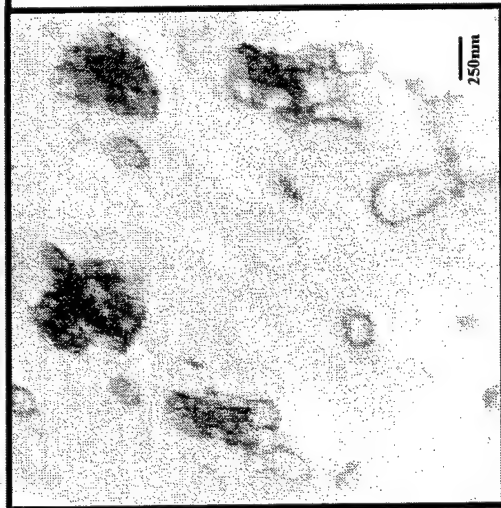
CyNorb(0-50)-random



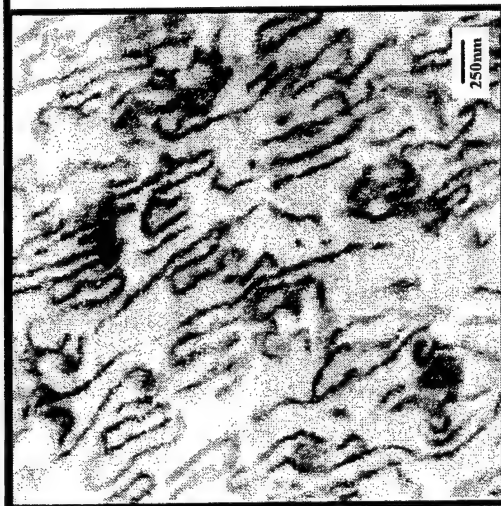
R = Cyclohexyl or Cyclopentyl



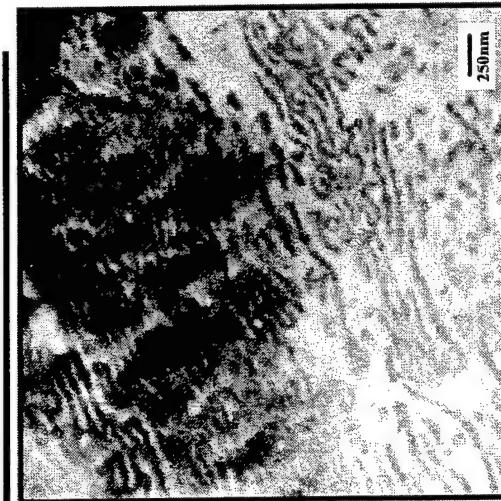
# TEM of Diblock POSS<sup>®</sup>-Norbornenes



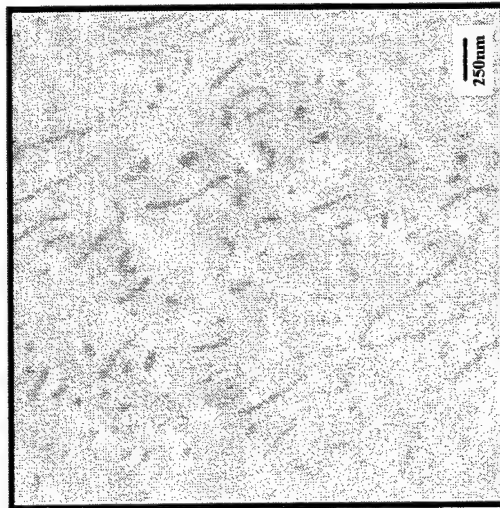
10wt % of CpPOSS



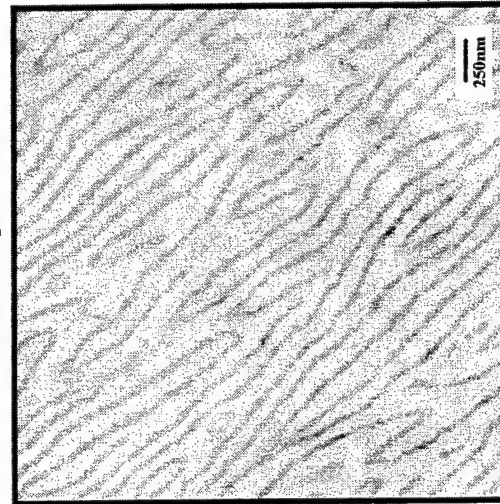
30wt % of CpPOSS



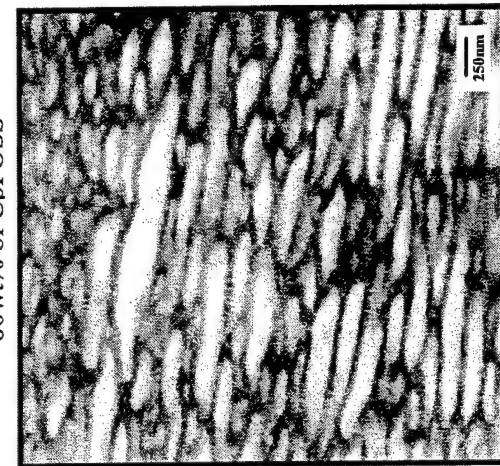
60wt % of CpPOSS



10wt % of CyPOSS



30wt % of CyPOSS



60wt % of CyPOSS

Pat Mather, AFRL

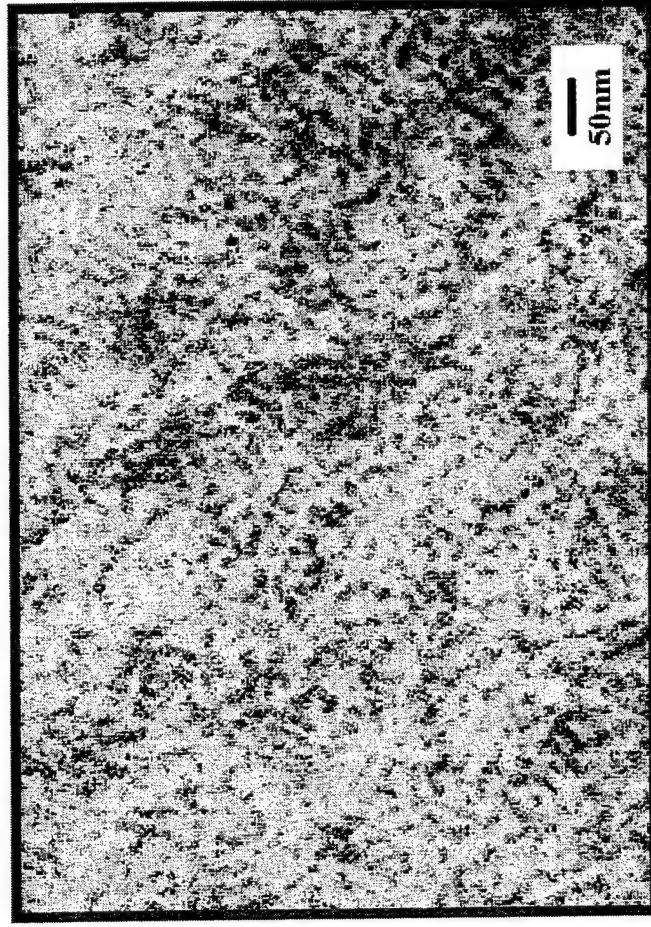




# TEM of Random POSS<sup>®</sup>-Norbornenes

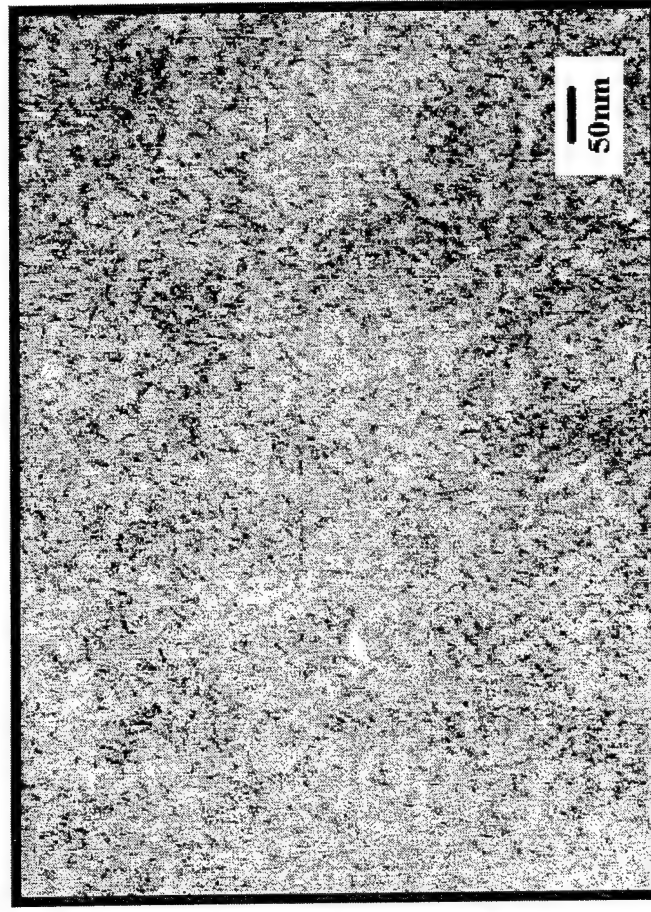


50CyPOSS/PN



“Coarse” Cylinder Nanostructure  
(Diameter ~ 12nm)

50CpPOSS/PN



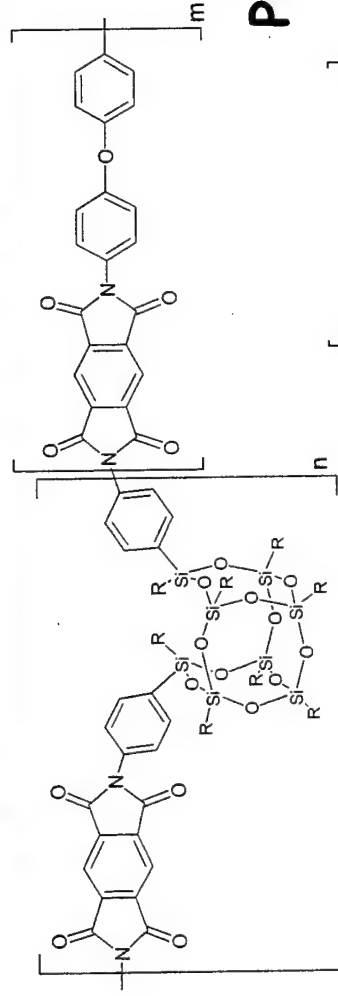
“Fine” Cylinder Nanostructure  
(Diameter ~ 6nm)

Since the glass transition improvement is almost double when R=cyclohexyl, then cyclohexyl POSS-rich domains may entrain more unoriented polynorbornene chains than Cyclopentyl POSS-rich domains.

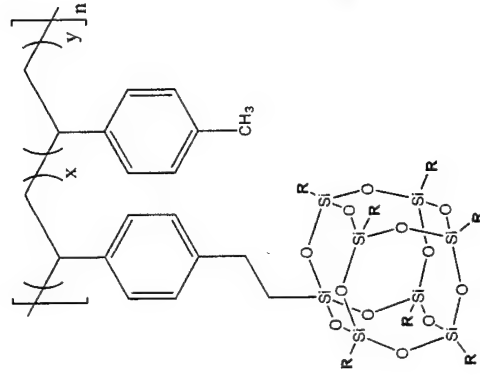




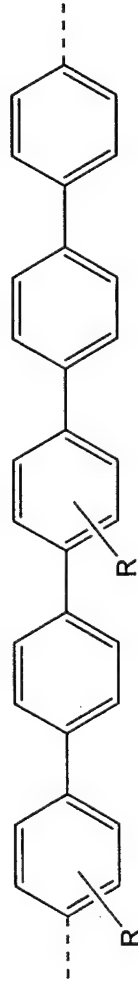
# Thermo/Mechanical Improvement of Polymers



**POSS<sup>®</sup> -Kapton<sup>®</sup> (polyimide)**



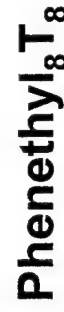
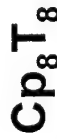
**POSS<sup>®</sup> -Styrenes**



**Maxdem's PARMAX<sup>™</sup> polymer**

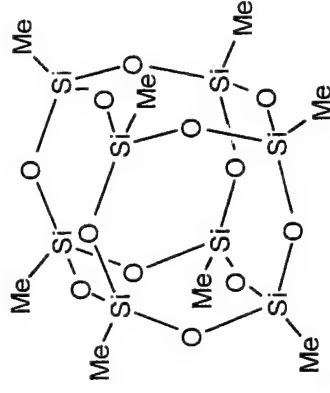
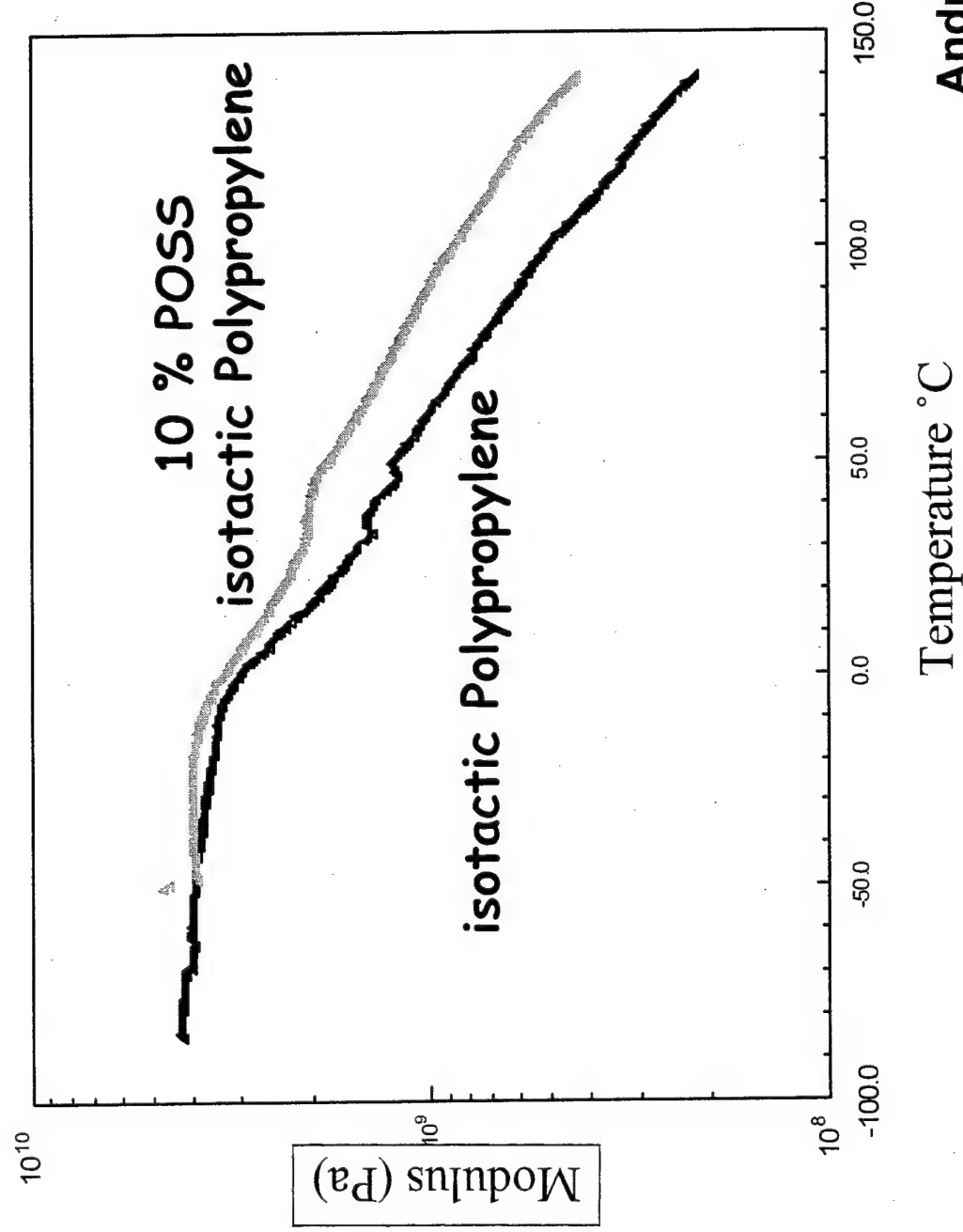


# 50 Wt % POSS Blends in 2 Million MW PS





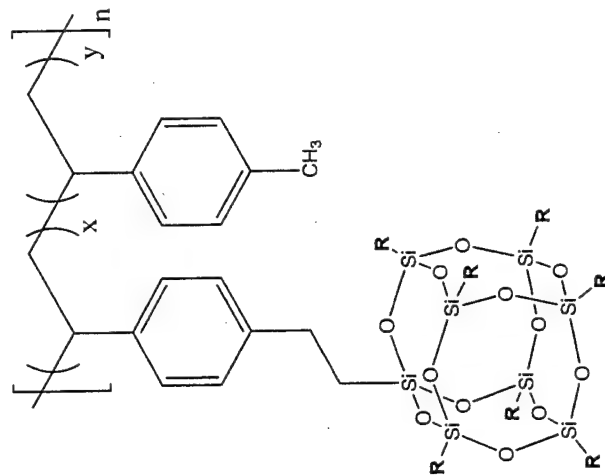
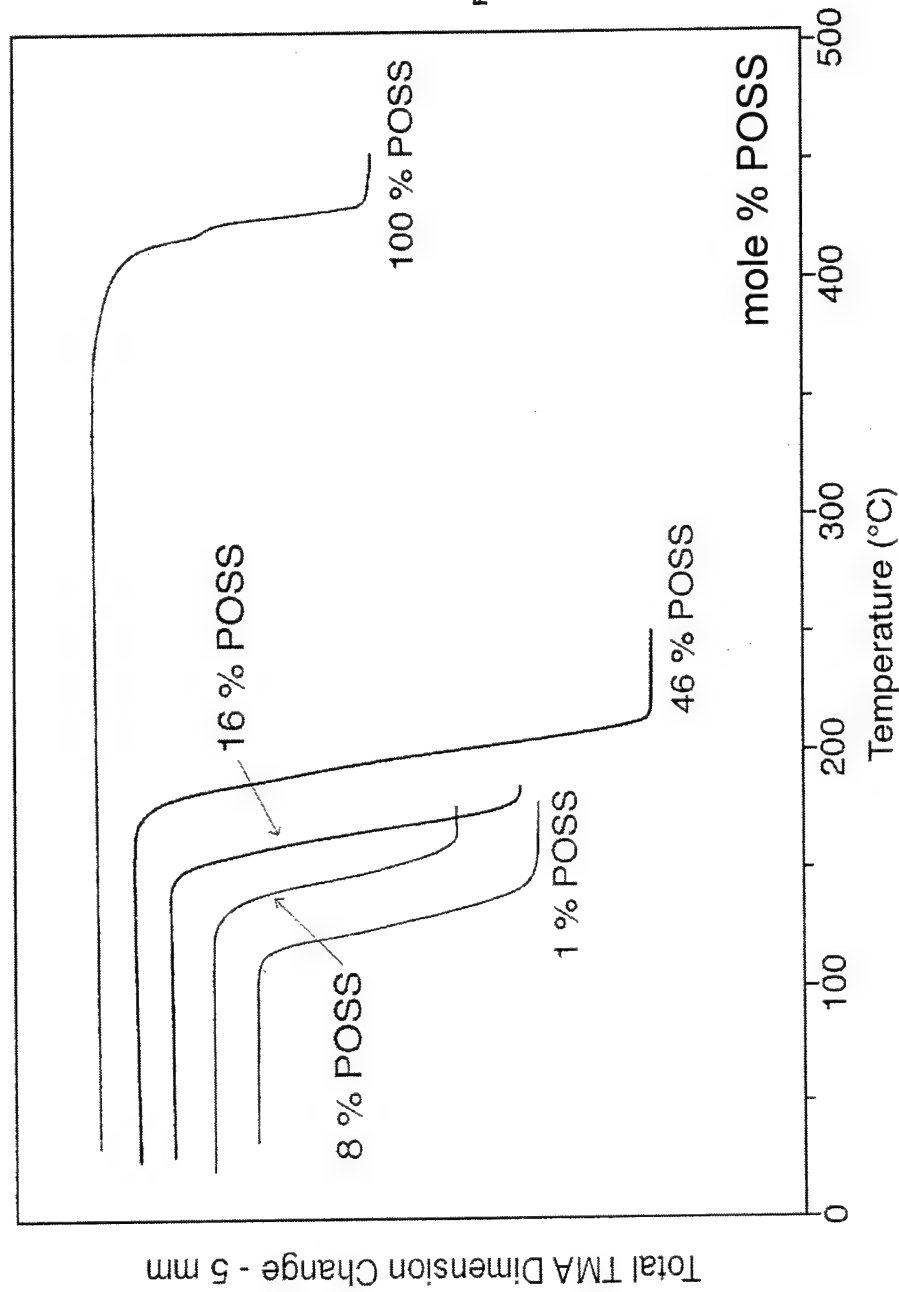
# DMA of 10 Wt% POSS<sup>®</sup> in isotactic Polypropylene



Andre Lee, AFRL

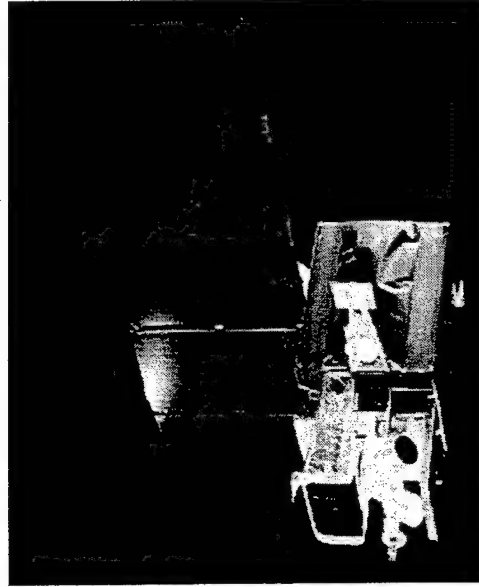


# TMA Plot For POSS<sup>®</sup> Styrenes (R = Cyclohexyl)

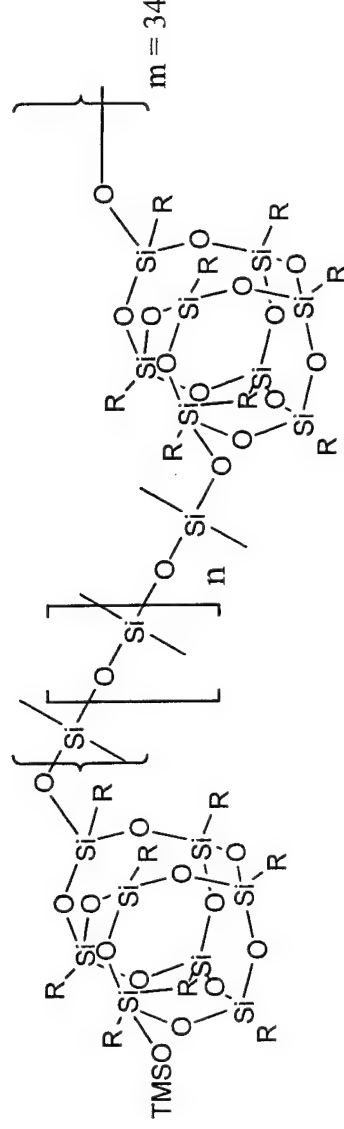
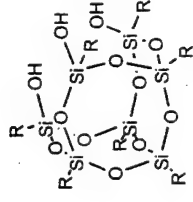


# POSS<sup>®</sup> Materials for Space

## Critical for Increasing Lifetime



Satellites & Space Systems



POSS<sup>®</sup>-PDMS copolymers

### POSS Nanocomposite Payoffs

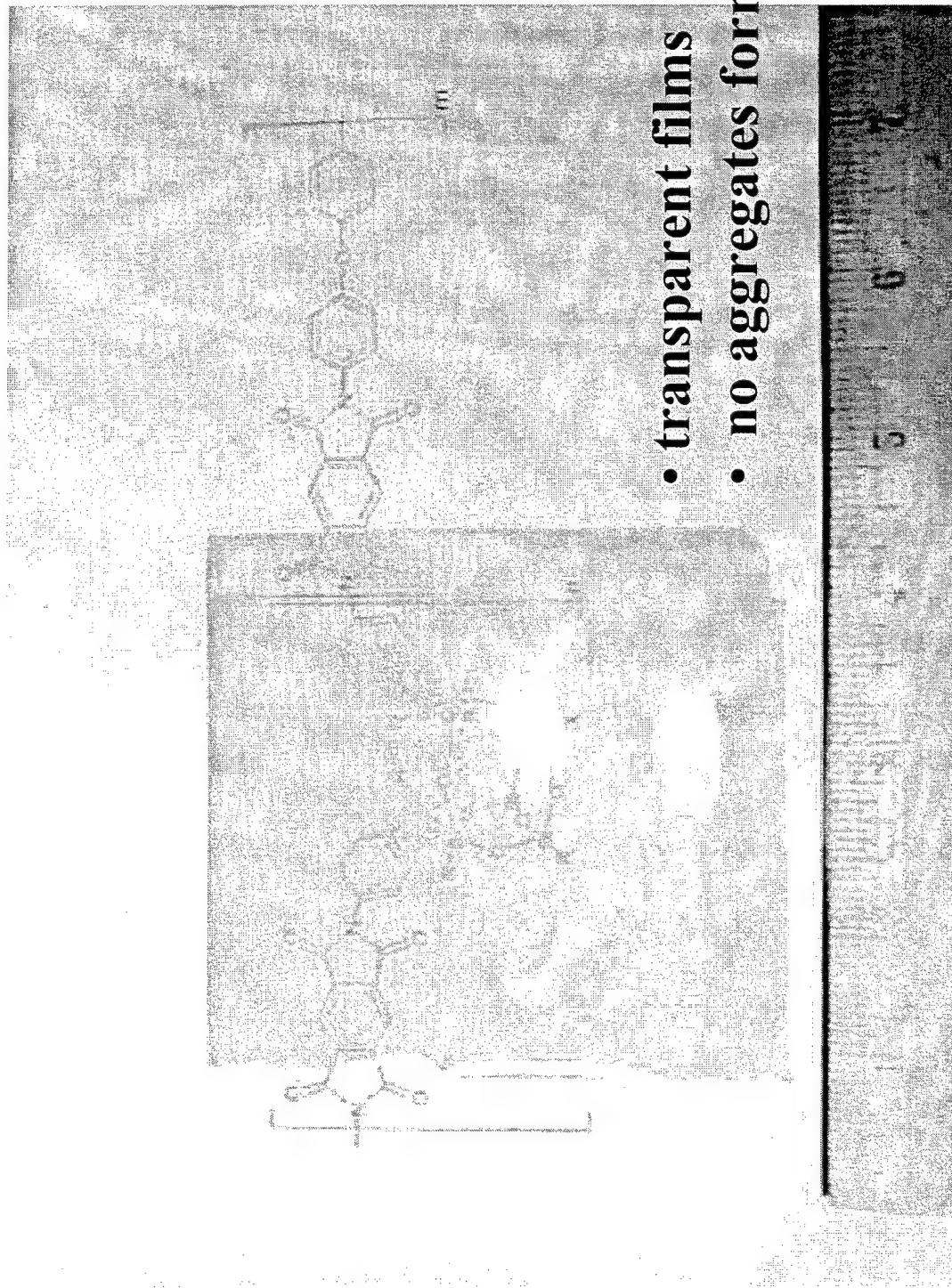
- Maximum Space Survivability
  - LEO, AO, VUV, Impact
- Lower Density 'Filler'
- High Modulus
- Resins for all Structural Applications

### Simulated 3 mo. AO/VUV Exposure

- 9-20x greater AO resistance than current state of art
- Even better AO/VUV resistance
- Passivation layer demonstrated



# POSS<sup>®</sup>-Kapton<sup>®</sup> Polyimides

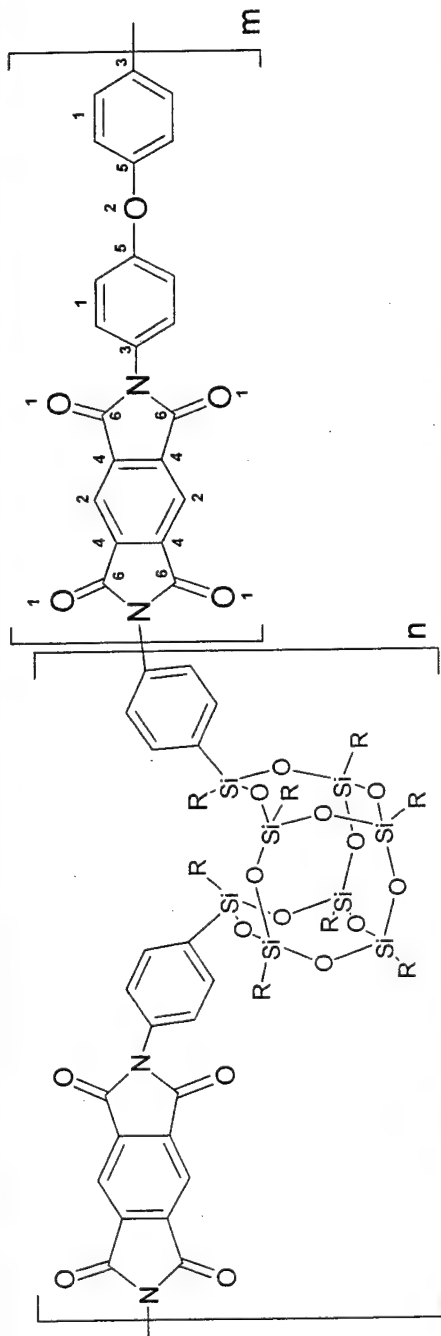


- transparent films
- no aggregates formed

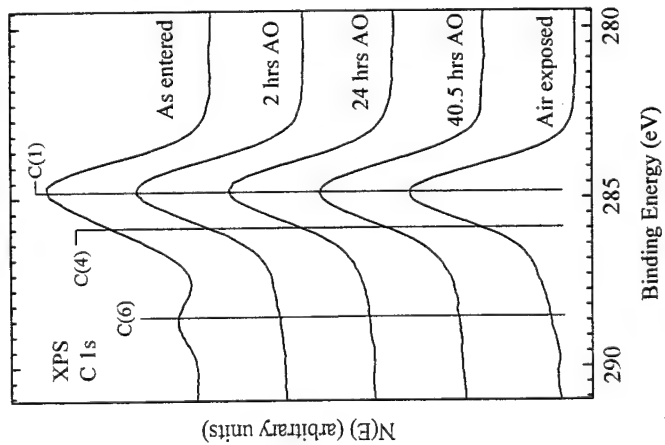




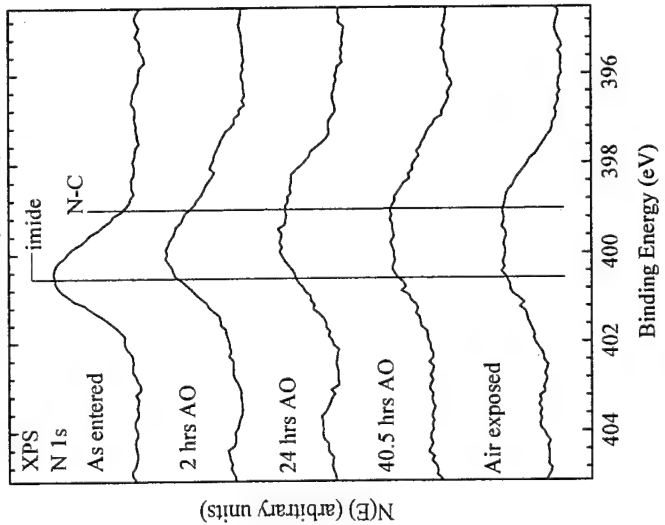
# Space-Survivable POSS<sup>®</sup>-polymers



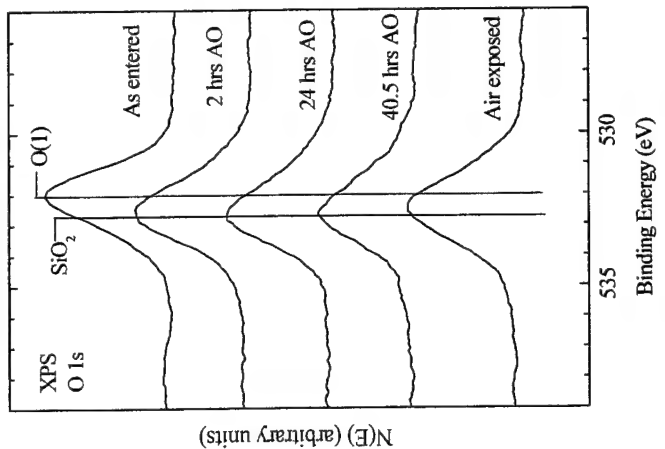
10wt% POSS-Kapton Polyimide



10wt% POSS-Kapton Polyimide



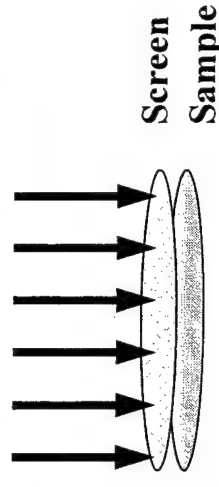
10wt% POSS-Kapton Polyimide





# Independent Verification of Oxidation Resistance

Hyperthermal AO Beam

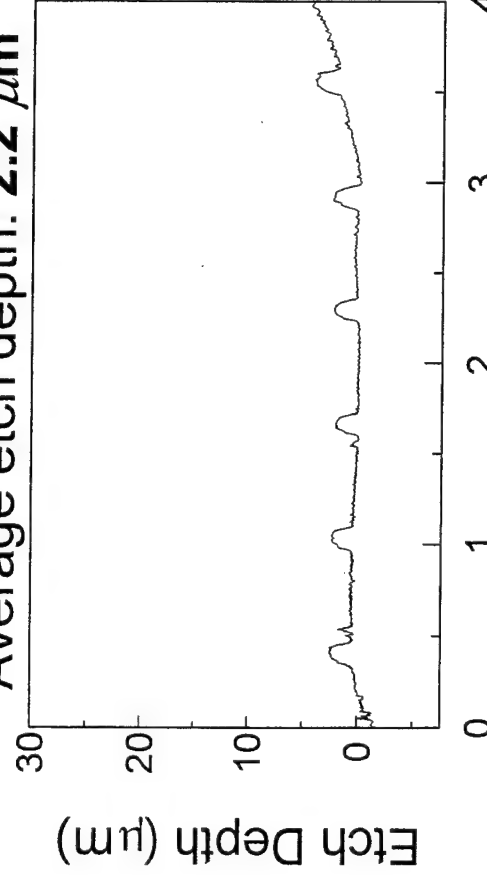


O-Atom Etching Experiment (~10 DAYS IN LEO)

Total AO fluence of  $8.47 \times 10^{20}$  atoms  $\text{cm}^{-2}$

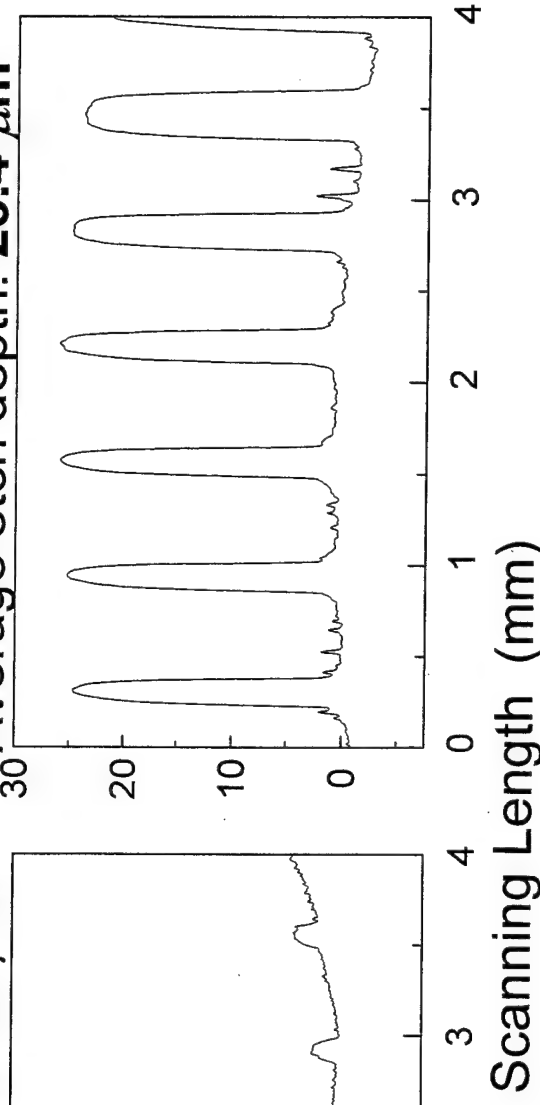
**Kapton 10 wt% POSS<sup>®</sup>**

Average etch depth:  $2.2 \mu\text{m}$



**Kapton H Standard**

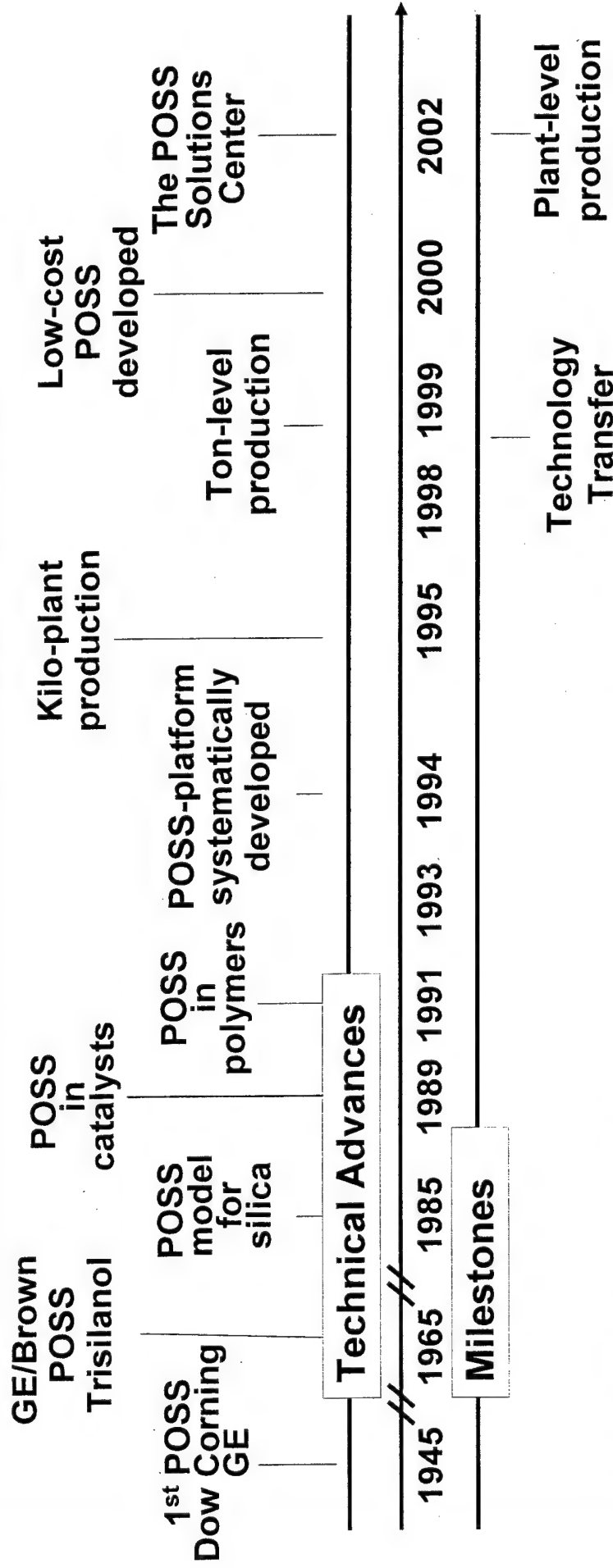
Average etch depth:  $25.4 \mu\text{m}$



Significantly improved oxidation resistance due to a rapidly formed, ceramic-like, passivating and **self-healing** silica layer preventing further degradation of underlying virgin polymer.

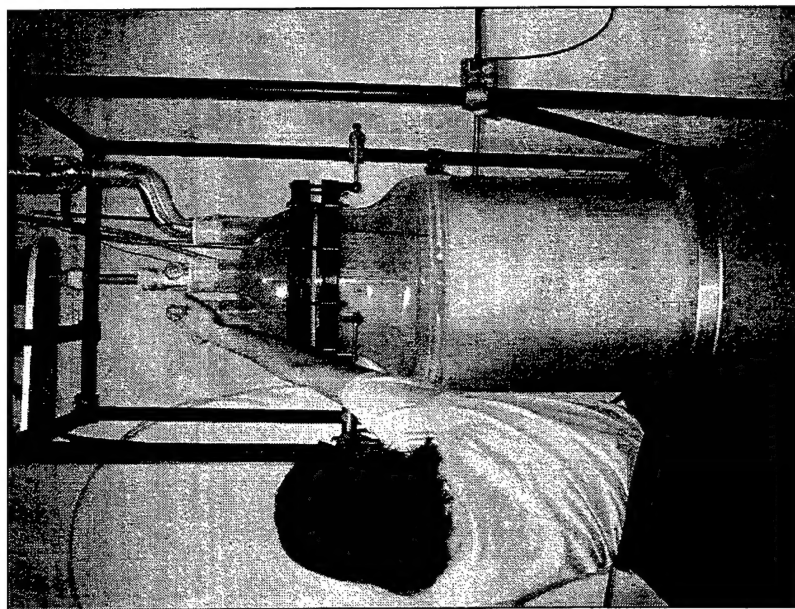
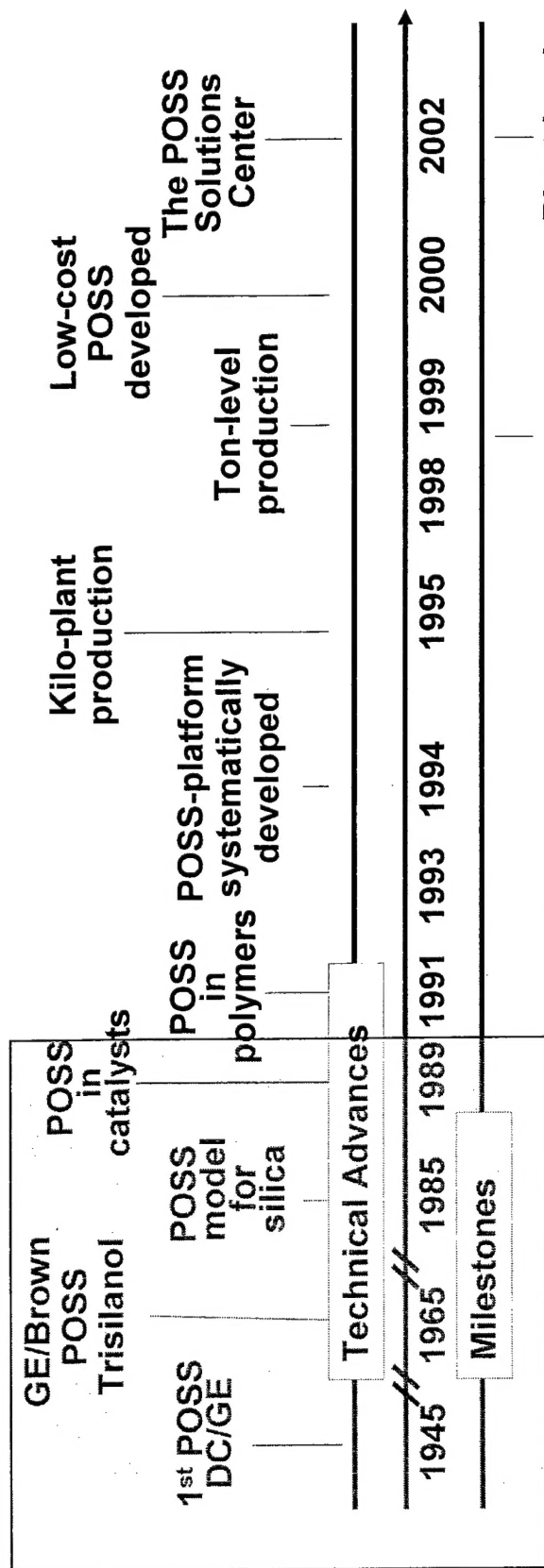
# Commercialization:

## POSS<sup>®</sup>-Technology Timeline

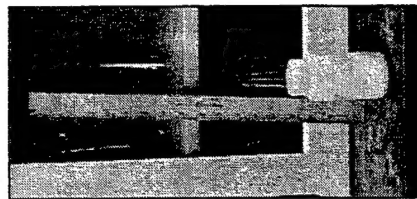


**UCL Air Force Hybrid Plastics**

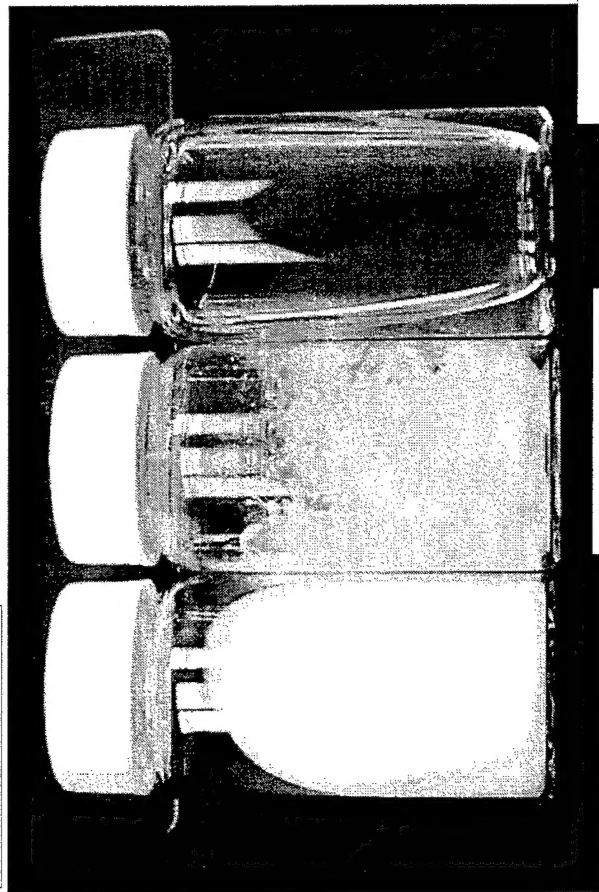
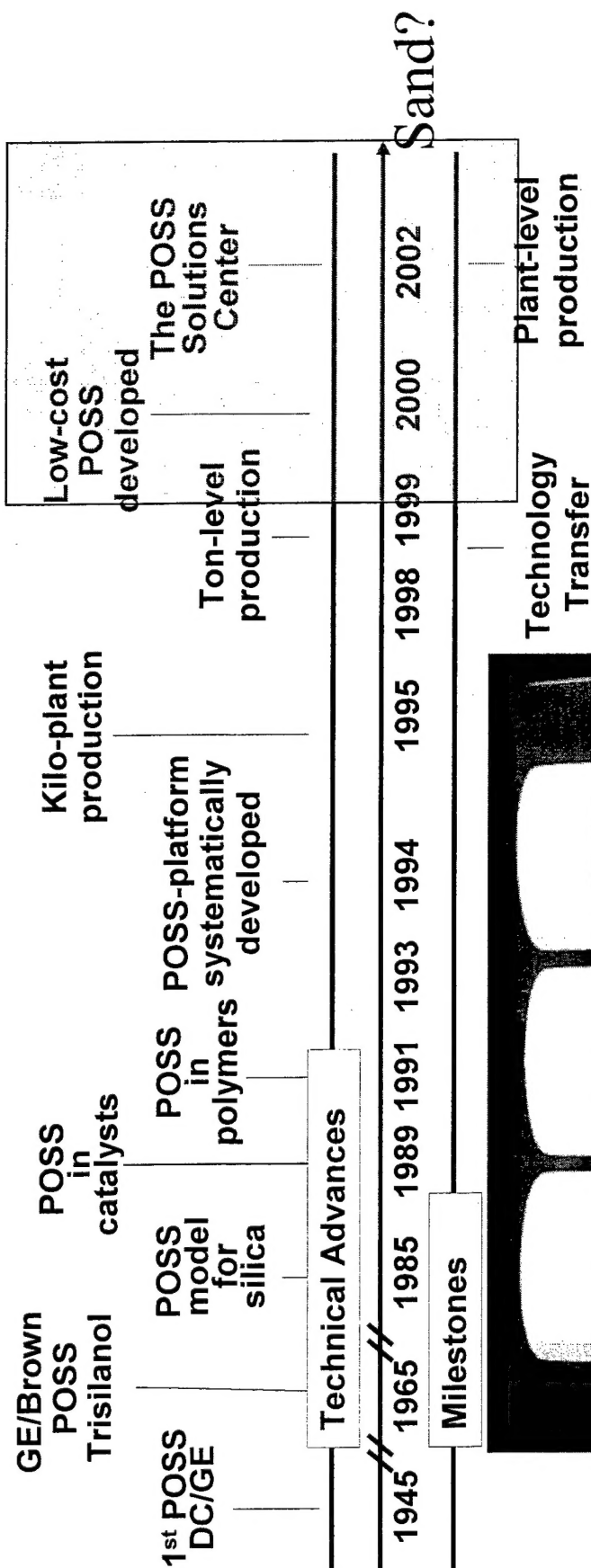
Chemistry      Polymers      Commercial Solutions



# Reverse Scale-up?







## Crystalline Solids

Wide melting range 24°C to 400°C+

## Waxes

## Liquids & Oils

Wide viscosity range 40cSt. to 400cSt

# POSS<sup>®</sup> Applications

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## R&D Through Market Development

### R&D Chemicals and

#### Nanotechnology Markets

Aldrich Chemical Co.

Gelest Inc.

Hybrid Plastics

### Monomers & Polymers

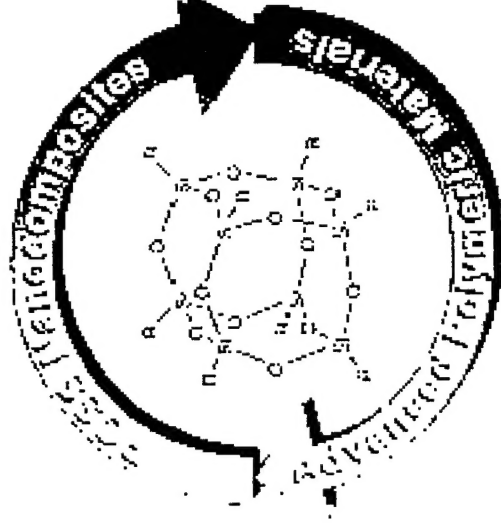
Aerospace

Electronics

Medical

Composites

Packaging



### Blendable Agents

Viscosity Modifiers

Processing Aids

Fire Retardants

Performance Additives

Corrosion Resistance

### Catalysis

Metathesis

Epoxidation

Ligands

Supports

### Biology & Agriculture

Drug Delivery

Medical Prosthetics

Pharmaceuticals

Antifungal Agents